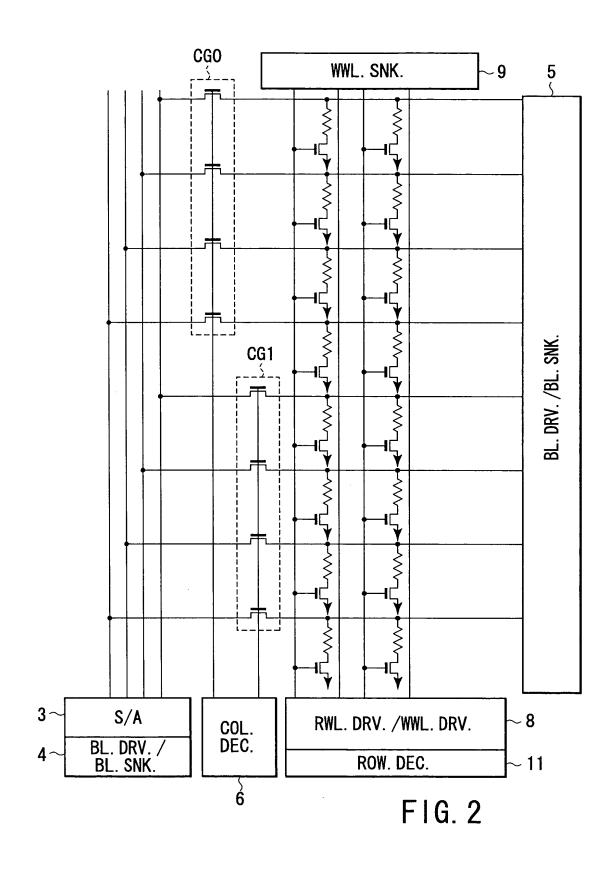


FIG. 1



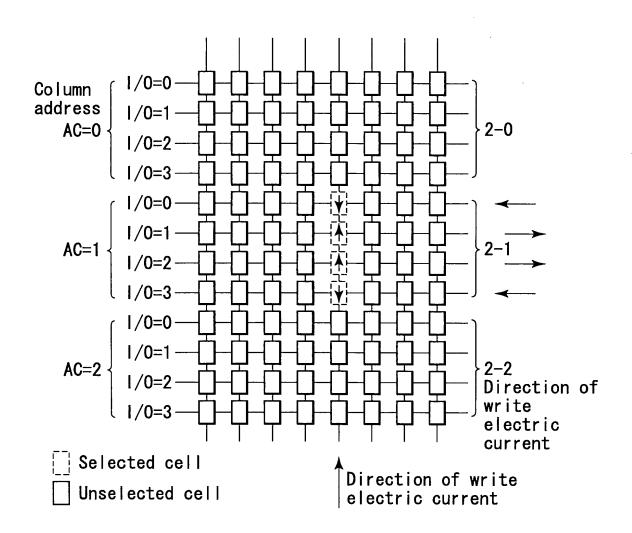
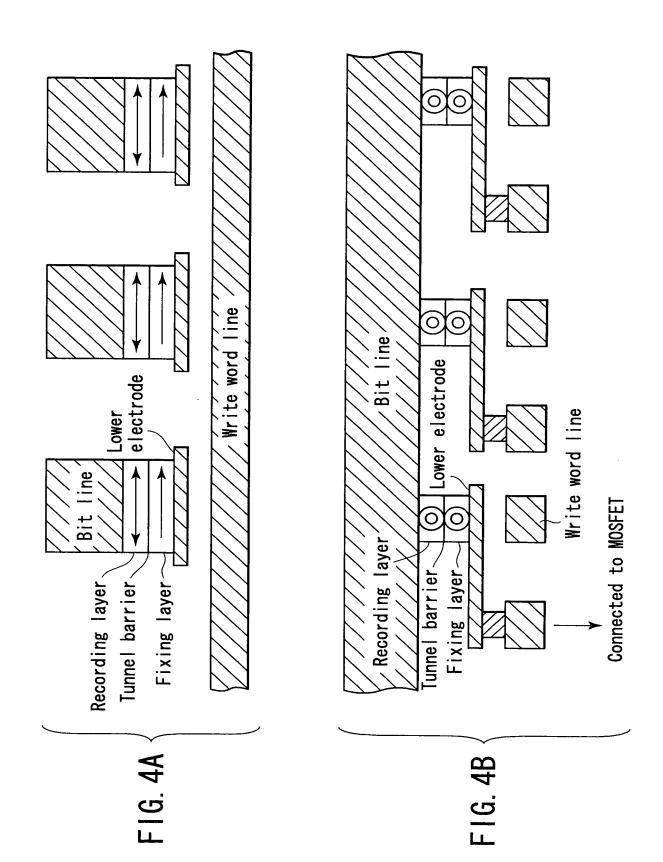
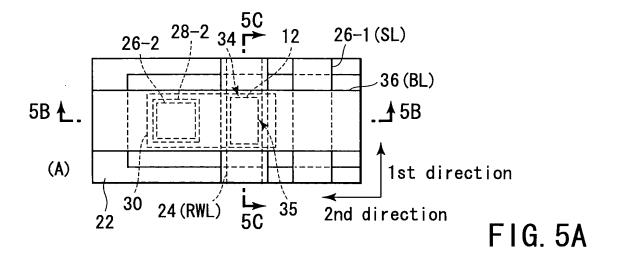
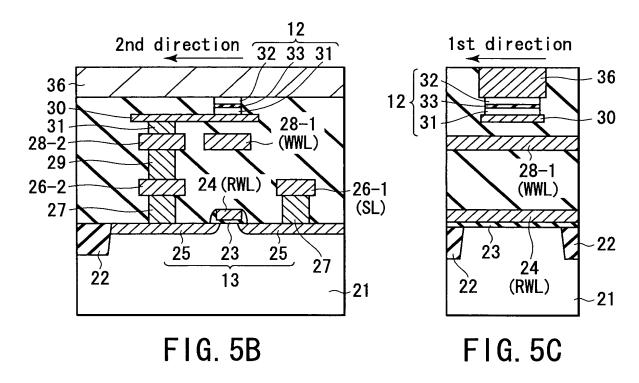
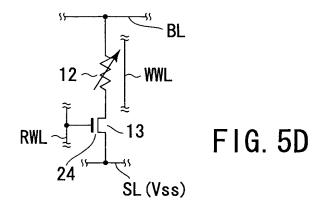


FIG. 3









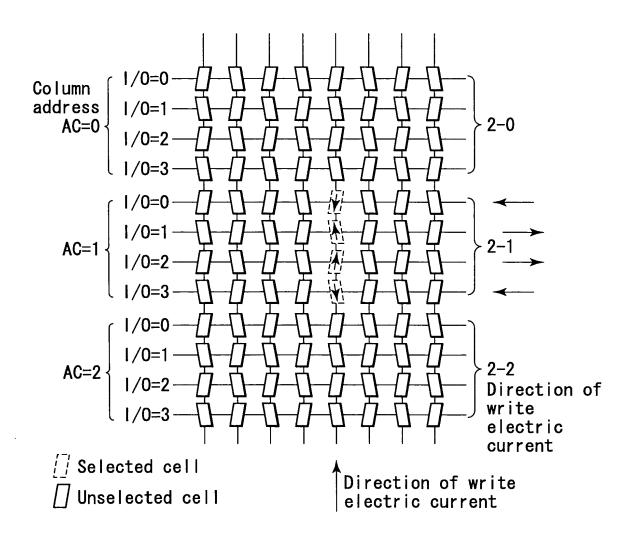


FIG. 6

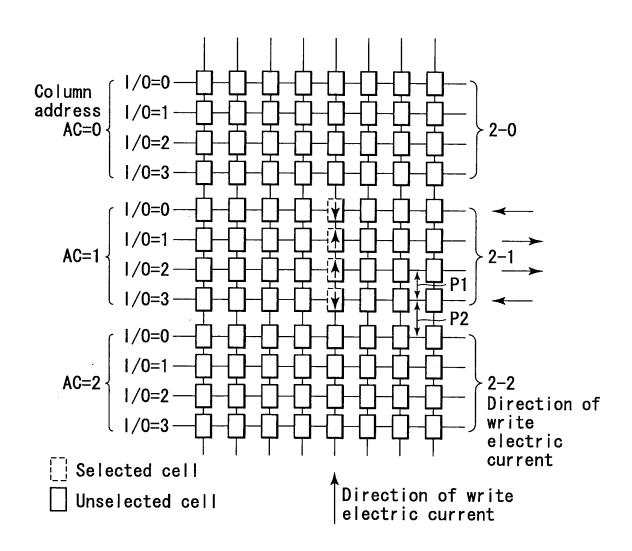
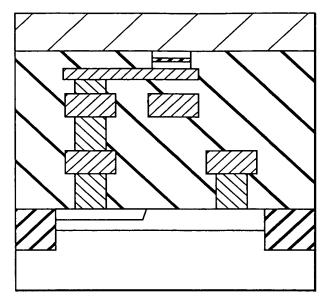
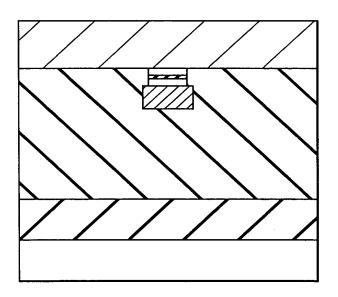


FIG. 7



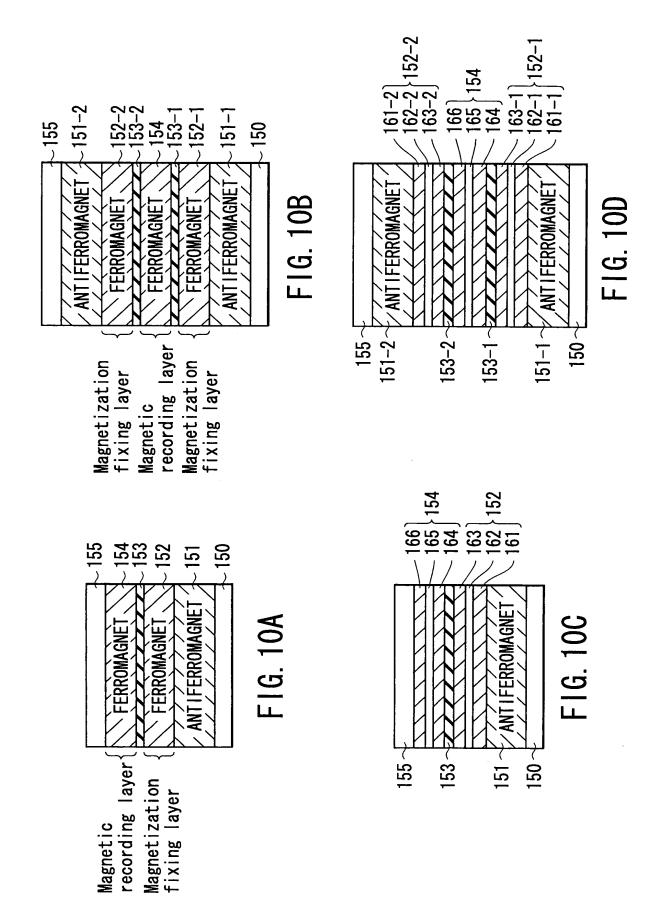
Cell using diode as switching element

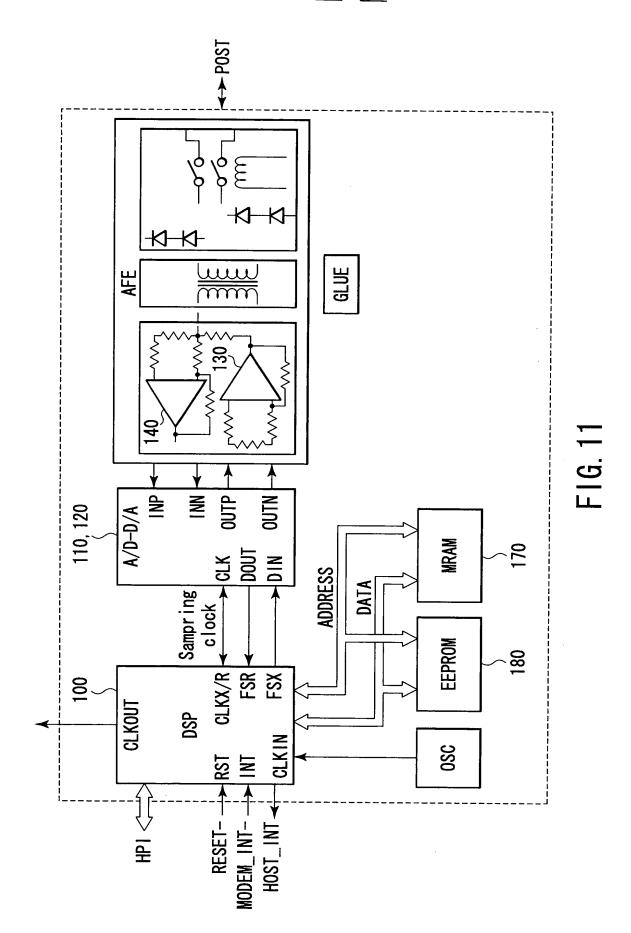
FIG. 8

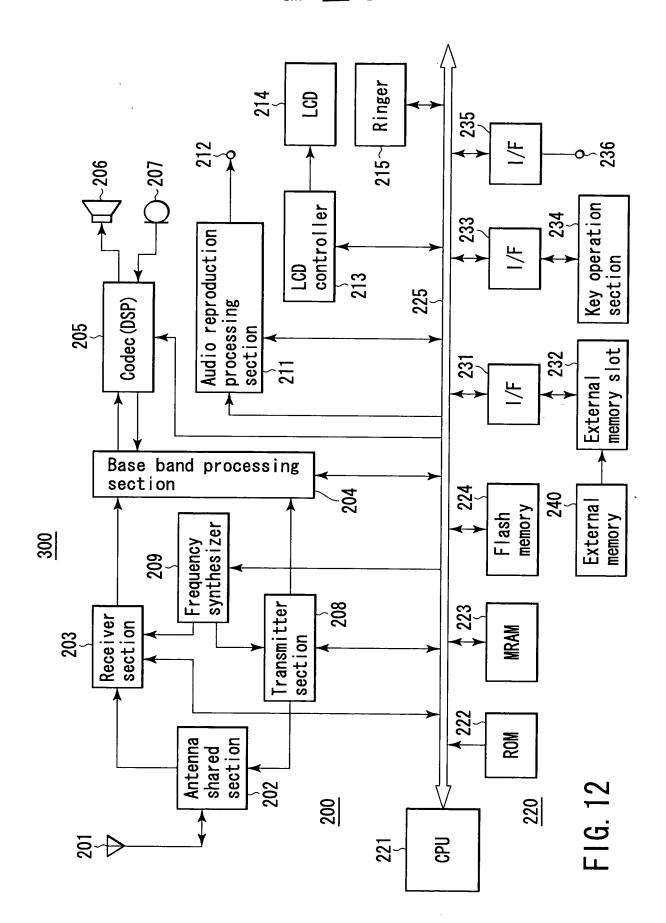


Cross point cell having no switching element

FIG. 9







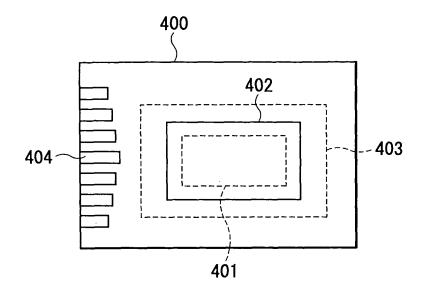
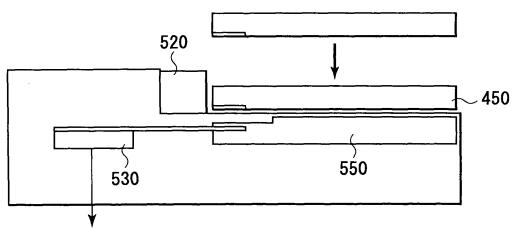
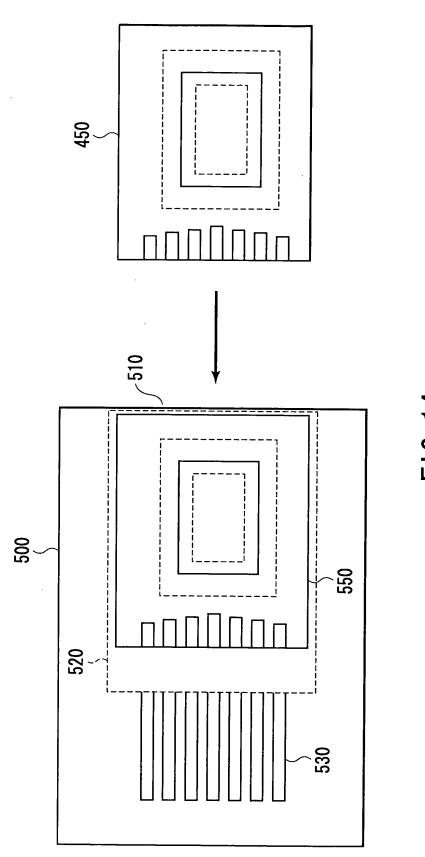


FIG. 13

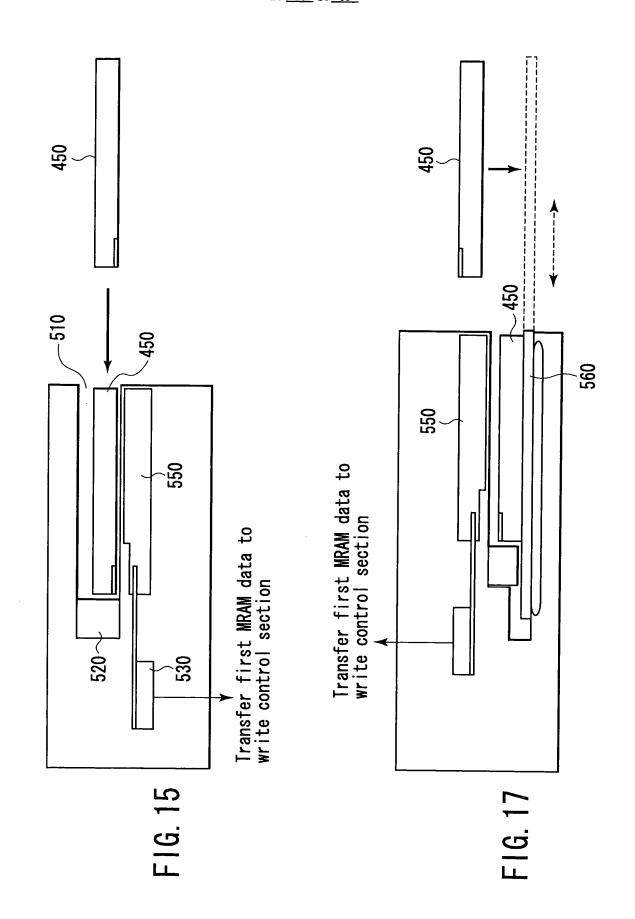


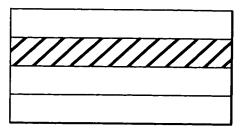
Transfer first MRAM data to write control section

FIG. 16



F1G. 14

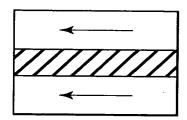




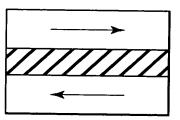
Ferromagnetic layer
Tunnel barrier
Ferromagnetic layer
Antiferromagnetic layer

TMR (tunnel magneto-resistive) element

FIG. 18



Parallel (small resistance)

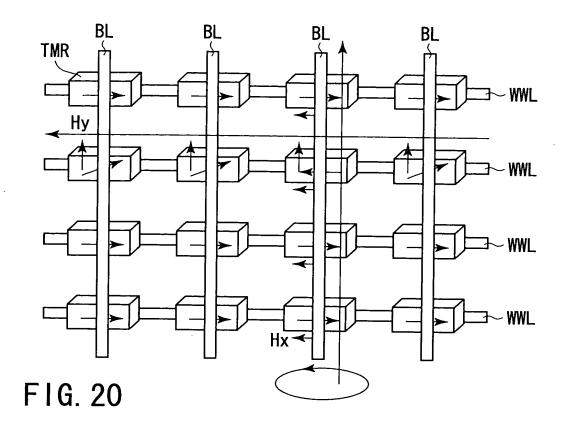


Opposite parallel (large resistance)

TMR Effect

FIG. 19A

FIG. 19B



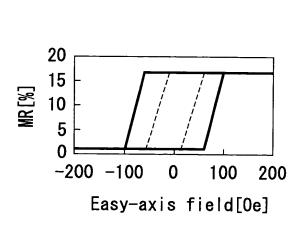


FIG. 21A

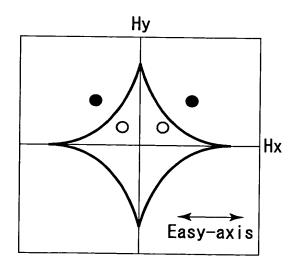


FIG. 21B